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IN THE U.S. PATENT AND TRADEMARK OFFICE

Applicant: Hiroshi ITATANI et al. Conf.: 9966  
Appl. No.: 09/980,212 Group: 1752  
Filed: March 18, 2002 Examiner: R. Ashton  
For: METHOD FOR FORMING POLYIMIDE PATTERN USING  
PHOTOSENSITIVE POLYIMIDE AND COMPOSITION THEREFOR

**AMENDMENT UNDER 37 C.F.R. § 1.312**

HANDCARRY TO:  
U.S. Patent and Trademark Office  
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Arlington, VA 22202

April 21, 2004

Sir:

Pursuant to the provisions of 37 C.F.R. § 1.312, the following amendments and remarks are respectfully submitted in connection with the above-identified application. It is respectfully requested that the following amendments be entered without withdrawing the application from issue.

**Amendments to the Claims** are reflected in the listing of claims which begins on page 2 of this paper.

**Remarks** begin on page 7 of this paper.

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15. (Canceled)

16. (Previously Presented) A method for forming negative-type pattern of polyimide comprising coating a substrate with the polyimide recited in claim 1; selectively irradiating the polyimide with an actinic ray, the irradiated regions constituting a desired pattern; and developing the irradiated polyimide with an alkaline solution to dissolve the non-irradiated regions.

17. (Original) The method according to claim 16, wherein said actinic ray is electron beam.

18. (Canceled)